



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of Chang Gyu KIM et al.	<ul><li>) METHOD FOR FORMING ISOLATION</li><li>) LAYER OF SEMICONDUCTOR DEVICE</li></ul>
Korean Application No. 2001-15415	, )
Korean Filing Date: March 24, 2001	) Group Art Unit: 2823
Serial No.: 10/001,314	) Examiner: N. Berezny )
Filed: November 14, 2001	) IECHI
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Commissioner for Patents	CEHI
P.O. Box 1450	
Alexandria VA 22313-1450	280

## **AMENDMENT**

Sir:

In response to the Office action of June 16, 2003, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.